ABSTRACT

EXPOSURE APPARATUS, EXPOSURE METHOD, AND ARTICLE MANUFACTURING METHOD

An exposure apparatus for projecting a pattern of an original onto a substrate by a projection optical system, and exposing the substrate, is provided. The apparatus includes a stage configured to move while holding the substrate, a measurement device configured to perform, at a plurality of measurement points in an exposure region, measurement of a height position of the substrate held by the stage, and a controller configured to control the measurement device, and correct a position of the stage based on a result of the measurement such that a shift amount of the height position with respect to an image plane of the projection optical system is decreased. The controller is configured to set the plurality of measurement points in the exposure region based on information regarding the exposure region.

(Fig. 1)